

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-AB20 (Also Form PTO-1449)

Date Considered

7/2/07

Examiner <u>M. Vugget</u>	Date Considered <u>7/2/07</u>
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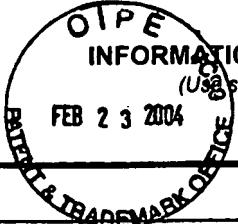
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INFORMATION DISCLOSURE CITATION <small>(Use several sheets if necessary)</small>				ATTY DOCKET NO. U6090-3	SERIAL NO. 10/046,594	
				Stephen Y. Chou FILING October 29, 2001	GROUP 1732	
U.S. PATENT DOCUMENTS						
*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
MJV	5,425,848	06/20/95	Haisma et al.			
↑	5,503,963	04/02/96	Bifano	↑		
	4,543,225	09/24/85	Beaujean			
	5,434,107	07/18/95	Paranjpe			
	5,338,396	08/16/94	Abdala et al.			
	5,471,455	11/28/95	Jabr			
	4,287,235	09/01/81	Flanders			
	4,512,848	04/23/85	Deckman et al.	↓		
MJV	5,259,926	11/09/93	Kuwabara et al.	—	—	
FOREIGN PATENT DOCUMENTS						
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
MJV		Kamins, T.I., "Positioning of Self-Assembled, single-crystal, germanium islands by silicon nanoimprinting" Applied Physics Letter, Vol. 74, No. 12, March 22, 1999				
MJV		Wang, J., et al., "Fabrication of a new broadband waveguide polarizer with a double-layer 190 nm period metal-gratings using nanolithography" J. Vac. Sci. Technol. B 17 (6) Nov/Dec 1999.				
EXAMINER <i>M. Vargot</i>			DATE CONSIDERED <i>7/2/07</i>			
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INFORMATION DISCLOSURE CITATION

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FEB 23 2004

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U6090-3

SERIAL NO.
10/046,594

Stephen Y. Chou

FILING

October 29, 2001

GROUP

1732

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (*Including Author, Title, Date, Pertinent Pages, Etc.*)

MoV		Tan, H., et al., "Roller Nanoimprint Lithography" Vac. Sci. Technol. B 16 (6) Nov/Dec 1998.
MoV		Feynman, Richard, "There's Plenty of Room at the Bottom-An Invitation to Enter a New Field of Physics" talk delivered at the annual meeting of the American Physical Society at the California Institute of Technology (Caltech) in 1959, published in February 1960 issue of Caltech's "Engineering and Science".

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<p style="text-align: center;">O I P E INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i></p> <p>FEB 23 2004</p>				ATTY DOCKET NO. U6090-3	SERIAL NO. 10/046,594		
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FOREIGN PATENT DOCUMENTS							
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						YES	NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
MDV			Healey et al., "Photodeposition of Micrometer-scale polymer patterns on optical imaging Fibers" Science Vol. 269, August 1995, pp. 1078-1080.				
EXAMINER	<i>M. Vugset</i>			DATE CONSIDERED		<i>7/2/07</i>	
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Sheet 1 of *p*

Form 1449*	Atty. Docket No.: 600.426US2	Serial No. Unknown
	Applicant: Stephen Y. Chou	
	Filing Date: Herewith	Group: Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
MDV	3,743,842	07/03/1973	Smith, H.I., et al.	250	320	01/14/72
	4,310,743	01/12/1982	Seliger, R.L.	219	121 EB	09/24/79
	4,325,779	04/20/1982	Rossetti, J.J.	156	651	11/17/80
	4,383,026	05/10/1983	Hall, T.M.	430	325	08/24/81
	4,450,358	05/22/1984	Reynolds, G.O.	250	492.1	09/22/82
	4,498,009	02/05/1985	Reynolds, G.O.	250	452.1	09/22/82
	4,516,253	05/07/1985	Novak, W.T.	378	034	04/25/83
	4,552,615	11/12/1985	Amendola, A., et al.	158	659.1	05/21/84
	4,576,678	03/18/1986	Shibata, H.	156	643	09/13/84
	4,606,788	08/19/1986	Moran, P.L.	156	656	04/03/85
	4,731,155	03/15/1988	Napoli, L.S., et al.	156	643	04/15/87
	4,832,790	05/23/1989	Rossetti, J.J.	156	651	02/24/87
	5,277,749	01/11/1994	Griffith, J.H., et al.	156	643	10/17/91
MDV	5,861,113	01/19/1999	Choquette, S.J., et al.	264	1.24	08/01/96

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes	No
MDV	1196749	01/30/1988	European	G11B	7/26		
	244884	03/28/1986	European	B29C	33/64		
	401196749	08/08/1989	Japan	G11B	7/26		
	4255307	09/10/1992	Japan	B29C	33/38		
	4332694	08/05/1991	European	B41N	1/12		
	9117565	11/14/1991	PCT	H01L	21/00		
MDV	98/26913	06/25/1998	PCT	B29C	33/58		

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

MDV	Broere, et al., "250-A Linewidths with PMMA Electron Resist", <u>Applied Physics Letter 33 (5)</u> , 1978 American Institute of Physics, 392-394, (September 1, 1978)
	Chou, S.Y., et al., "Imprint Lithography with 25-Nanometer Resolution", <u>Science</u> , Vol 272, 85-87, (April 5, 1996)
	Early, K., et al., "Absence of Resolution Degradation in X-Ray Lithography for Wavelength from 4.5nm to 0.83nm", <u>Microelectronic Engineering 11</u> , Elsevier Science Publishers B.V., 317-321, (1990)
MDV	Fischer, et al., "10 nm Electron Beam Lithography and sub-50 nm Overlay Using a Modified Scanning Electron Microscope", <u>Applied Physics Letter 62 (23)</u> , 1993 American Institute of Physics, 2989-2991, (June 7, 1993)

Examiner A. Vugay

Date Considered

7/2/07

*Substitute Disclosure Statement Form (PTO-1449)

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Sheet 2 of *P*

Form 1449 INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Atty. Docket No.: 600.426US2	Serial No. Unknown
	Applicant: Stephen Y. Chou	
	Filing Date: Herewith	Group: Unknown

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

**Examiner
Initials

MOV	Hara, et al., "An Alignment Technique Using Diffracted Moire Signals", <u>J. Vac. Sci. Technol. B 7 (6)</u> , 1989 American Vacuum Society, 1977-1979, (Nov./Dec. 1989)
	Harmening, et al., "Molding of Threedimensional Microstructures by the Liga Process", <u>Proceedings IEEE : Micro Electro Mechanical Systems</u> , Travemunde, Germany, 202-207, (1992)
	Li, et al., "Molding of Plastic Components Using Micro-EDM Tools", <u>IEEE/CHMT International Electronics Manufacturing Technology Symposium</u> , 145-149, (1992)
MOV	Nomura, et al., "Moire Alignment Technique for the Mix and Match Lithographic System", <u>J. Vacuum Society Technol. B 6 (1)</u> , American Vacuum Society, 394-398, (Jan/Feb 1988)

Examiner <u>M. Vayart</u>	Date Considered <u>7/2/07</u>
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